

L Number	Hits	Search Text	DB	Time stamp
-	6	(("4671851") or ("4910155") or ("4944836") or ("5244523") or ("5209816") or ("5340370")).PN.	USPAT	2002/04/12 13:57
-	55339	257/\$.ccls.	USPAT	2002/04/12 14:09
-	45861	438/\$.ccls.	USPAT	2002/04/12 14:09
-	45861	438/\$.ccls.	USPAT	2002/04/12 14:09
-	75855	156/\$.ccls.	USPAT	2002/04/12 14:10
-	36	(257/\$.ccls. 438/\$.ccls. 438/\$.ccls. 156/\$.ccls. ) and (h2o2 h?sub.2 adj o?sub.2 hydrogen adj peroxide) and (benzotriazole bta poly\$1acryl\$3 poly\$1methyl\$1acryl\$3 tri\$1ethanolamine mono\$1ethanolamine tri\$1ethyl\$1amine di\$1iso\$1propanolamine) and (phosphoric ortho\$1phosphoric h3po4 h?sub.3 adj po?sub.3)	USPAT	2002/04/12 15:41
-	36	(257/\$.ccls. 438/\$.ccls. 438/\$.ccls. 156/\$.ccls. ) and (h2o2 h?sub.2 adj o?sub.2 hydrogen adj peroxide) and (benzotriazole bta poly\$1acryl\$3 poly\$1methyl\$1acryl\$3 tri\$1ethanolamine mono\$1ethanolamine tri\$1ethyl\$1amine di\$1iso\$1propanolamine) and (phosphoric ortho\$1phosphoric h3po4 h?sub.3 adj po?sub.3)	USPAT	2002/04/12 16:06
-	882	(257/\$.ccls. 438/\$.ccls. 438/\$.ccls. 156/\$.ccls. ) and (polish\$3 same (metal\$3 copper cu al aluminum w tungsten) same (abrasive abradant\$1 particle\$1 particulate\$1 grain\$1 powder\$2))	USPAT	2002/04/12 16:13
-	227	((257/\$.ccls. 438/\$.ccls. 438/\$.ccls. 156/\$.ccls. ) and (polish\$3 same (metal\$3 copper cu al aluminum w tungsten) same (abrasive abradant\$1 particle\$1 particulate\$1 grain\$1 powder\$2)) ) and ((free no without) near5 (abrasive abradant\$1 particle\$1 particulate\$1 grain\$1 powder\$2))	USPAT	2002/04/12 16:14

L Number	Hits	Search Text	DB	Time stamp
1	166	( poly\$1acryl\$3 acrylate) near50 (cmp polish\$3)	USPAT; JPO	2002/04/21 08:13
4	29	(( poly\$1acryl\$3 acrylate) near50 (cmp polish\$3)) and (( poly\$1acryl\$3 acrylate) near30 (oxid\$5 peroxide))	USPAT; JPO	2002/04/21 08:18
7	6589	(( poly\$1acryl\$3 acrylate) and (cmp polish\$3)) not (( poly\$1acryl\$3 acrylate) near50 (cmp polish\$3))	USPAT; JPO	2002/04/21 08:15
10	689	(( ( poly\$1acryl\$3 acrylate) and (cmp polish\$3)) not (( poly\$1acryl\$3 acrylate) near50 (cmp polish\$3))) and semiconduct\$3	USPAT; JPO	2002/04/21 08:16
13	104	(( ( poly\$1acryl\$3 acrylate) and (cmp polish\$3)) not (( poly\$1acryl\$3 acrylate) near50 (cmp polish\$3))) and semiconduct\$3 and (( poly\$1acryl\$3 acrylate) near30 (oxid\$5 peroxide))	USPAT; JPO	2002/04/21 08:19